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TRANSMITTAL FORM

(to be used for all correspondence after initial filing)

Application Number	**10/729,169**
Filing Date	**December 4, 2003**
First Named Inventor	**Robert David ALLEN et al.**
Art Unit	**1713**
Examiner Name	**Unassigned**
Attorney Docket Number	**ARC920030103US1**

Mail Stop

ENCLOSURES (Check all that apply)

- ☒ No fee due
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- ☒ Supplemental Information Disclosure Statement & Form PTO-1449
  - ☒ Copies of cited references
- ☐ Certified Copy of Priority Document(s)
- ☐ Response to Missing Parts / Incomplete Application
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- ☐ Drawing(s)
- ☐ Licensing-related Papers
- ☐ Petition
- ☐ Petition to Convert to a Provisional Application
- ☐ Power of Attorney, Revocation, Change of Correspondence Address
- ☐ Terminal Disclaimer
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- ☐ CD, Number of CD(s):
- ☐ After Allowance Communication to a Technology Center (TC)
- ☐ Appeal Communication to Board of Appeals and Interferences
- ☐ Appeal Communication to TC (Appeal Notice, Brief, Reply Brief)
- ☐ Proprietary Information
- ☐ Status Letter
- ☐ Other Enclosure(s) (please identify below):

Remarks:

SIGNATURE OF APPLICANT, ATTORNEY, OR AGENT

Firm or Individual Name (print/type)	**Mark L. Warzel, Registration No. 47,264 Reed & Eberle LLP**	Telephone	**(650) 330-0900**
Signature		Date	**April 19, 2004**

CERTIFICATE OF TRANSMISSION/MAILING

I hereby certify that this correspondence is being deposited with the United States Postal Service with sufficient postage as first class mail in an envelope addressed to: Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450 on the date shown below.

Name (print/type)	**Will Sayo**		
Signature		Date	**April 19, 2004**

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In Re Application of:
Robert David ALLEN et al.

Serial No.: 10/729,169

Filing Date: December 4, 2003

Title: LOW ACTIVATION ENERGY PHOTORESISTS

Confirmation No.: 8945

Group Art Unit: 1713

Examiner: Unassigned

SUPPLEMENTAL INFORMATION DISCLOSURE STATEMENT

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

This is a Supplemental Information Disclosure Statement submitted for the Examiner's consideration. Applicants respectfully request that the Examiner review and make of record the references identified below.

A PTO-1449 form listing the references accompanies this paper. Applicants request that the Examiner kindly initial and return to them a copy of the form to indicate that the references have been reviewed and made of record. The references are as follows:

U.S. PATENT DOCUMENT		
Document No.	Issue Date or Publication Date	Name of Patentee or Applicant
4,356,296	10/26/82	Griffith et al.
4,365,049	12/21/82	Tsunoda et al.
4,452,998	6/5/84	Griffith et al.
6,027,856	2/22/00	Nozaki et al.
6,074,801	6/13/00	Iwasa et al.
6,106,998	8/22/00	Maeda et al.
6,140,010	10/31/00	Iwasa et al.
6,146,806	11/14/00	Maeda et al.
6,319,650	11/20/01	Gelorme et al.
Serial No. 10/604,082	Filed 6/25/03	Hinsberg et al.

FOREIGN PATENT DOCUMENT		
Document No.	Publication Date	Country
JP 61281116 A	11/12/86	Japan

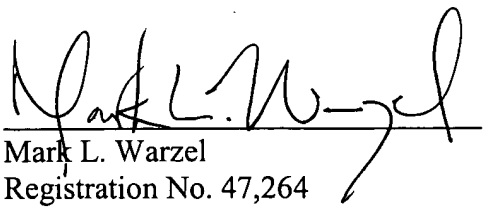
NONPATENT DOCUMENTS
ALLEN et al. (1997), "Deep-UV Resist Technology: The Evolution of Materials and Processes for 250-nm Lithography and Beyond," *Handbook of Microlithography, Micromachining, and Microfabrication Volume 1: Microlithography*, Chapter 4, pp. 321-375, P. Rai-Choudhury, Editor, SPIE Optical Engineering Press..
FEDYNYSHYN et al. (2001), "High Resolution Fluorocarbon Based Resist for 157-nm Lithography," *Advances in Resist Technology And Processing XVIII, Proceedings of SPIE* 4345:296-307.
KODAMA et al. (2002), "Synthesis of Novel Fluoropolymer for 157nm Photoresists by Cyclo-Polymerization," *Advances in Resist Technology and Processing XIX, Proceedings of SPIE* 4690:76-83.
REICHMANIS et al. (1991), "Chemical Amplification Mechanisms for Microlithography," *Chem. Mater.* 3(3):394-407
URRY et al. (1968), "Multiple Multicenter Reactions of Perfluoro Ketones with Olefins," *The Journal of Organic Chemistry* 33(6):2302-2310.

As the subject application was filed after June 30, 2003, copies of the U.S. patents disclosed in this Supplemental Information Disclosure Statement are not required and, therefore, are not included.

This Supplemental Information Disclosure Statement is not intended as a representation that a search has been made, that additional information material to the examination of this application does not exist, or that any of the above references constitutes prior art to the present application within the meaning of 35 USC § 102.

As applicants have not yet received a first Action on the merits, no fee is required for filing this Supplemental Information Disclosure Statement. If, however, the PTO finds that for some reason a fee is found to be necessary, our Deposit Account No. 18-0580 may be charged therefor.

Respectfully submitted,

By: 

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Substitute for form 1449A/PTO

INFORMATION DISCLOSURE STATEMENT BY APPLICANT

(use as many sheets as necessary)

Sheet 1 of 1

Complete if Known	
Application Number	10/729,169
Filing Date	December 4, 2003
First Named Inventor	Robert David ALLEN et al.
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Attorney Docket Number	ARC920030103US1

U.S. PATENT DOCUMENTS

Examiner Initials*	Cite No.	Document No.	Issue Date or Publication Date	Name of Patentee or Applicant of Cited Document	Class	Subclass	Filing Date if Appropriate
	AR	4,356,296	10/26/82	Griffith et al.			
	AS	4,365,049	12/21/82	Tsunoda et al.			
	AT	4,452,998	6/5/84	Griffith et al.			
	AU	6,027,856	2/22/00	Nozaki et al.			
	AV	6,074,801	6/13/00	Iwasa et al.			
	AW	6,106,998	8/22/00	Maeda et al.			
	AX	6,140,010	10/31/00	Iwasa et al.			
	AY	6,146,806	11/14/00	Maeda et al.			
	AZ	6,319,650	11/20/01	Gelorme et al.			
	BA	Serial No. 10/604,082	Filed 6/25/03	Hinsberg et al.			

FOREIGN PATENT DOCUMENTS

Examiner Initials*	Cite No.	Foreign Patent Document No.	Publication Date	Country	Class	Subclass	T
	BB	JP 61281116 A	11/12/86	Japan			

OTHER DOCUMENTS — NONPATENT LITERATURE DOCUMENTS

Examiner Initials*	Cite No.	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), Title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	T
	BC	ALLEN et al. (1997), "Deep-UV Resist Technology: The Evolution of Materials and Processes for 250-nm Lithography and Beyond," *Handbook of Microlithography, Micromachining, and Microfabrication Volume 1: Microlithography*, Chapter 4, pp. 321-375, P. Rai-Choudhury, Editor, SPIE Optical Engineering Press..	
	BD	FEDYNYSHYN et al. (2001), "High Resolution Fluorocarbon Based Resist for 157-nm Lithography," *Advances in Resist Technology And Processing XVIII, Proceedings of SPIE* 4345:296-307.	
	BE	KODAMA et al. (2002), "Synthesis of Novel Fluoropolymer for 157nm Photoresists by Cyclo-Polymerization," *Advances in Resist Technology and Processing XIX, Proceedings of SPIE* 4690:76-83.	
	BF	REICHMANIS et al. (1991), "Chemical Amplification Mechanisms for Microlithography," *Chem. Mater.* 3(3):394-407	
	BG	URRY et al. (1968), "Multiple Multicenter Reactions of Perfluoro Ketones with Olefins," *The Journal of Organic Chemistry* 33(6):2302-2310.	

Examiner Signature		Date Considered	

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.